

SEP 10 2007

Docket No.: 020732-97.668 (7493)
Appl. No. 10/792,038

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of:		Docket No.:	020732-97.668 (7493)
Applicants:	RATH, Melissa K., et al.	Conf. No.:	4823
Application No.:	10/792,038	Art Unit:	1752
Date Filed:	March 3, 2004	Examiner:	LE, Hoa Van
Title:	COMPOSITION AND PROCESS FOR POST-ETCH REMOVAL OF PHOTORESIST AND/OR SACRIFICIAL ANTI-REFLECTIVE MATERIAL DEPOSITED ON A SUBSTRATE	Customer No.:	24239

FACSIMILE TRANSMISSION CERTIFICATE

Attn: Examiner Hoa Van Le

Fax No. (571) 273-8300

I hereby certify that this document is being filed in the United States Patent and Trademark Office, via facsimile transmission to Mail Stop AF, Commissioner for Patents, PO Box 1450, Alexandria, VA 22313-1450, on September 10, 2007, to United States Patent and Trademark Office facsimile transmission number (571) 273-8300.

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Number of Pages (including cover)

Tristan A. Fuierer

September 10, 2007

Date _____

**AMENDMENT RESPONDING TO JULY 9, 2007 OFFICE ACTION AND SUPPLEMENTAL
INFORMATION DISCLOSURE STATEMENT IN UNITED STATES PATENT
APPLICATION NO. 10/792,038**

**Mail Stop AF
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450**

Sir:

This responds to the July 9, 2007 Office Action in the above-identified application.

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Please amend the claims, as set out in the following **Section I (the Claims)**.

Remarks addressing the substance of the July 9, 2007 Office Action are set out in the **Section II (Remarks)** hereof.

A Supplemental Information Disclosure Statement and Certification Statement are enclosed and concurrently submitted herewith.